Amendments to the Claims:

This listing of claims will replace all prior versions, and listings, of claims in the application:

Listing of Claims:

Claims 1 - 6 (canceled)

Claims 7 - 11 (canceled)

12. (previously presented) A vacuum processing apparatus comprising:

a transfer box inside of which an object wafer to be processed is transferred under an atmospheric condition by a transfer robot disposed therein, the transfer box having a plurality of wafer cassettes installed at a front surface portion thereof;

a vacuum transfer chamber disposed at a rear surface portion of the transfer box and detachably connected thereto, the vacuum transfer chamber enabling transfer of the object wafer therein under a vacuum condition;

at least one vacuum processing chamber disposed at a rear or side of the vacuum transfer chamber and being connected thereto, the at least one vacuum processing chamber being supplied with gas and enabling processing of the object wafer transferred under the vacuum condition by a plasma generated therein; and

a plurality of connector portions of utility paths being disposed substantially linearly under a connecting portion of the transfer box and the vacuum transfer chamber, and being disposed at the rear surface portion of the transfer box;

wherein the utility paths enable supply of utilities including the gas supplied from a building having the vacuum processing apparatus installed therein to the vacuum transfer chamber or the vacuum processing chamber and enables discharge

of exhaust from the vacuum transfer chamber or the vacuum processing chamber including the utilities supplied thereto.

13. (previously presented) A vacuum processing apparatus comprising:

an atmospheric block including a transfer box inside of which an object wafer to be processed is transferred under an atmospheric condition by a transfer robot disposed therein, the transfer box having a plurality of wafer cassettes installed at a front surface portion thereof;

a vacuum transfer chamber disposed at a rear surface portion of the transfer box and detachably connected thereto, the vacuum transfer chamber enabling transfer of the object wafer therein under a vacuum condition;

a vacuum processing block, installed at a connecting portion of the vacuum transfer chamber and the transfer box;

at least one vacuum processing chamber of the vacuum processing block being disposed at a rear or side of the vacuum transfer chamber and being connected thereto, the at least one vacuum processing transfer being supplied with gas and enabling processing of the object wafer transferred under the vacuum condition by a plasma generated therein; and

a plurality of connector portions of utility paths being disposed substantially linearly under a connecting portion of the transfer box and the vacuum transfer chamber, and being disposed at the rear surface portion of the transfer box;

wherein the utility paths enables supply of utilities including the gas supplied from a building having the vacuum processing apparatus installed therein to the vacuum transfer chamber or the vacuum processing chamber and enable discharge

of exhaust from the vacuum transfer chamber or the vacuum processing chamber including the utilities supplied thereto.

14. (previously presented) The vacuum processing apparatus according to claim 12, wherein the utilities include plural kinds of gases, water, air supplied from the building.

15. (previously presented) The vacuum processing apparatus according to claim 14, wherein the connector portions of the utility paths connect with paths arranged under a floor of the building in which the vacuum processing apparatus is installed.

16. (previously presented) The vacuum processing apparatus according to claim 15, wherein the connector portions of the utility paths are disposed under at least one load lock chamber consisting of the connecting portion between the transfer box and the vacuum transfer chamber.

17. (previously presented) The vacuum processing apparatus according to claim 14, wherein the connector portions of the utility paths are disposed under at least one load lock chamber consisting of the connection portion between the transfer box and the vacuum transfer chamber.

18. (previously presented) The vacuum processing apparatus according to claim 14, further comprising display units disposed at the rear surface portion of the transfer box and enable display of a status of the utility.

19. (currently amended) The vacuum processing apparatus according to claim ~~19~~ 13, wherein the utilities include plural kinds of gases, water, air supplied arranged the building.

20. (currently amended) The vacuum processing apparatus according to claim ~~20~~ 19, wherein the connector portions of the utility paths connect with paths from under a floor of the building in which the vacuum processing apparatus is installed.

21. (currently amended) The vacuum processing apparatus according to claim ~~19~~ 20, wherein the connector portions of the utility paths are disposed under at least one load lock chamber consisting of the connecting portion between the transfer box and the vacuum transfer chamber.

22. (previously presented) The vacuum processing apparatus according to claim 19, wherein the connector portions of the utility paths are disposed under at least one load lock chamber consisting of the connection portion between the transfer box and the vacuum transfer chamber.

23. (previously presented) The vacuum processing apparatus according to claim 13, further comprising display units disposed at the rear surface portion of the transfer box and enable display of a status of the utility.